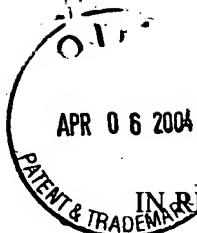


04-07-04

Express Mail No. ER452516100US
Attorney Docket No.: AM-5264.D1



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Cheng Guo et al.

SERIAL NO.: 10/792,011

FILED: March 3, 2004

FOR: STRUCTURES USEFUL IN ELECTRON BEAM
LITHOGRAPHY

§ GROUP ART UNIT: 1756
§ (Parent Application)

§ EXAMINER: S. R. Mohamedulla
§ (Parent Application)

§ Attorney Docket No.:
§ AM-5264.D1

Date: April 6, 2004

INFORMATION DISCLOSURE STATEMENT
TRANSMITTAL LETTER

Hon. Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450


Sir:

Applicants are submitting the subject Information Disclosure Statement under 37 CFR § 1.97(b)(1). This Information Disclosure Statement is being submitted within three (3) months of the filing date of the subject application.

CERTIFICATE OF MAILING UNDER 37 CFR § 1.10

I hereby certify that this paper is being deposited with the U.S. Postal Service on the date shown below with sufficient postage as U.S. EXPRESS MAIL NO. ER452516100US in an envelope addressed to: Mail Stop DD, Commissioner for Patents, Alexandria, VA 22313-1450


Date: April 6, 2004


Shirley L. Church, Reg. No. 31,858

Applicants do not believe that any fee is due in connection with the filing of this Information Disclosure Statement under 37 CFR § 1.97(b)(1). However, in the event that any additional fee is due, the Commissioner is hereby authorized to charge Deposit Account No. 50-1512 of Shirley L. Church, Sunnyvale, California, in the amount of such fee.

This transmittal letter is submitted in duplicate for accounting purposes.

Respectfully submitted,


Shirley L. Church
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FORM PTO-1449 U.S. Department of Commerce
(Equivalent) Patent and Trademark Office

U.S. Application Serial No.
10/792,011

Atty. Docket No.
AM-5264.D1

INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

(Use several sheets if necessary)

Cheng Guo et al.
Applicants

March 3, 2004
Filing Date

1756
Group

U. S. PATENT DOCUMENTS

Examiner Initial	Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
_____	4,827,138	05/02/89	Randall *	250	492.2 R	
_____	5,899,728	05/04/99	Mangat et al. *	438	459	
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

- _____ S. D. Berger et al., "New approach to projection-electron lithography with demonstrated 0.1 μ m linewidth", Applied Physics Letters, Vol. 57, No. 2, pp. 153-155 (July 1990).
- _____ S. D. Berger et al., "Projection electron-beam lithography: A new approach", J. Vac. Sci. Technol. B, Vol. 9, No. 6, pp. 2996-2999 (Nov/Dec 1991).

Examiner Date Considered

Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

* Cited by the Examiner during the prosecution of the parent application, U.S. Serial No. 09/698,706.